



*Supplement of*

## **Confined fission-track revelation in apatite: how it works and why it matters**

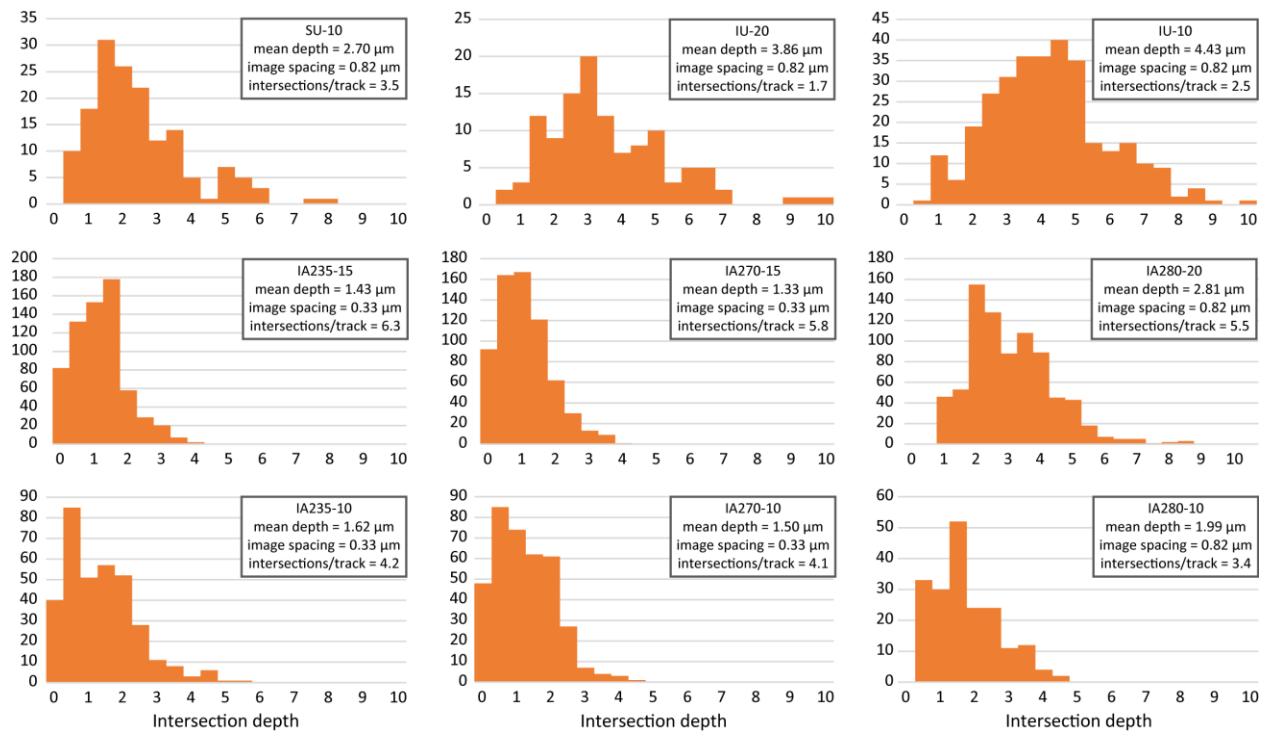
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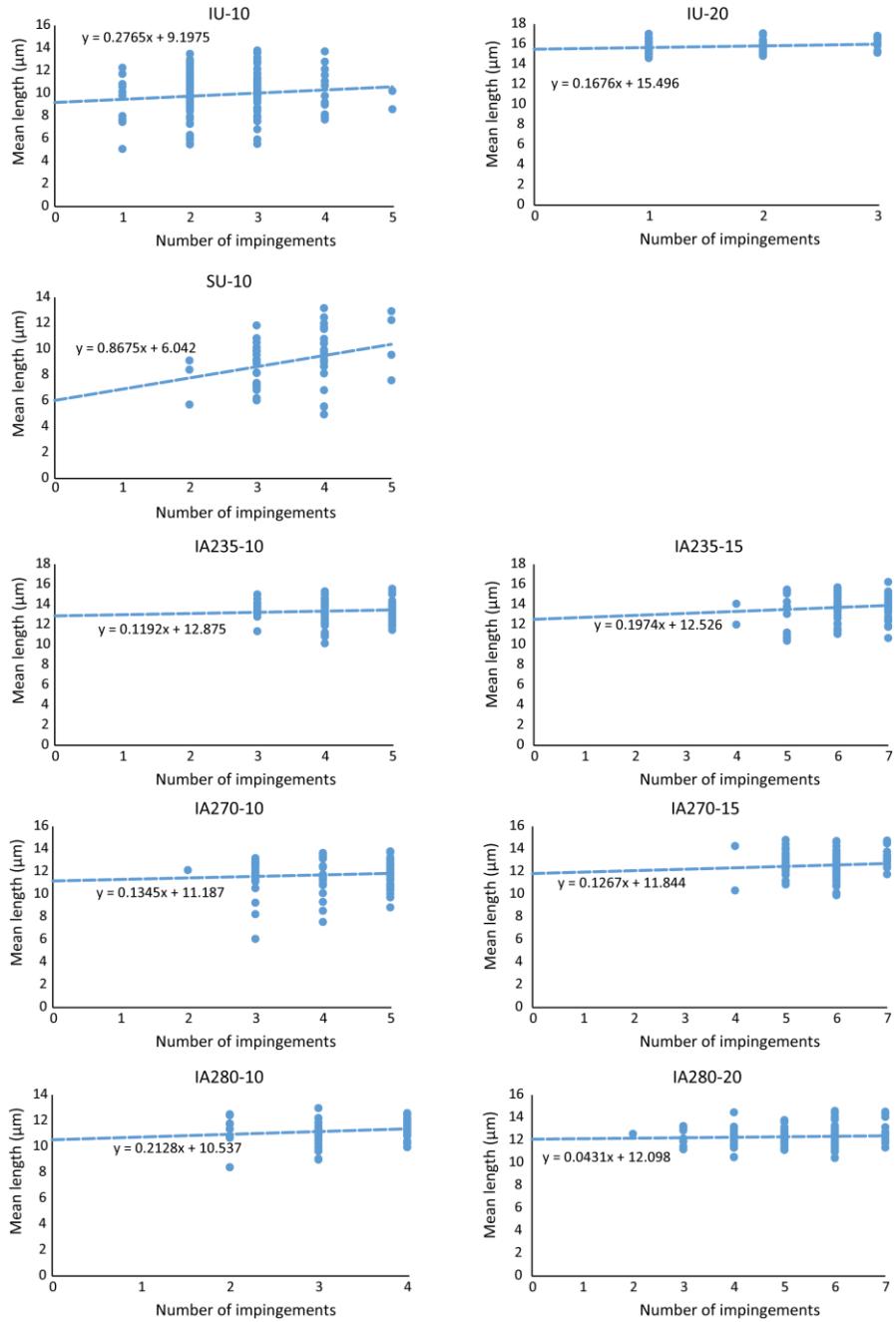
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## **Introduction**

This file contains supplemental figures S-1 and S-2. It also contains model outputs for each data set fitted, using the diagrams demonstrated in Figures 6, 7, 10, and 11 of the manuscript, using the Constant-core model. Also included are the plots of the measured track length histograms for the earliest etching steps, for comparison with model predictions, and the command line to run the model in the IDL code (see statement on Code Availability), and the text output for each etching step, as: mean length ( $\mu\text{m}$ ), standard deviation ( $\mu\text{m}$ ), number of tracks selected, mean latent length of selected tracks, mean starting time of etching  $t_s$  (s), and mean impingement depth  $z_{int}$  ( $\mu\text{m}$ ).

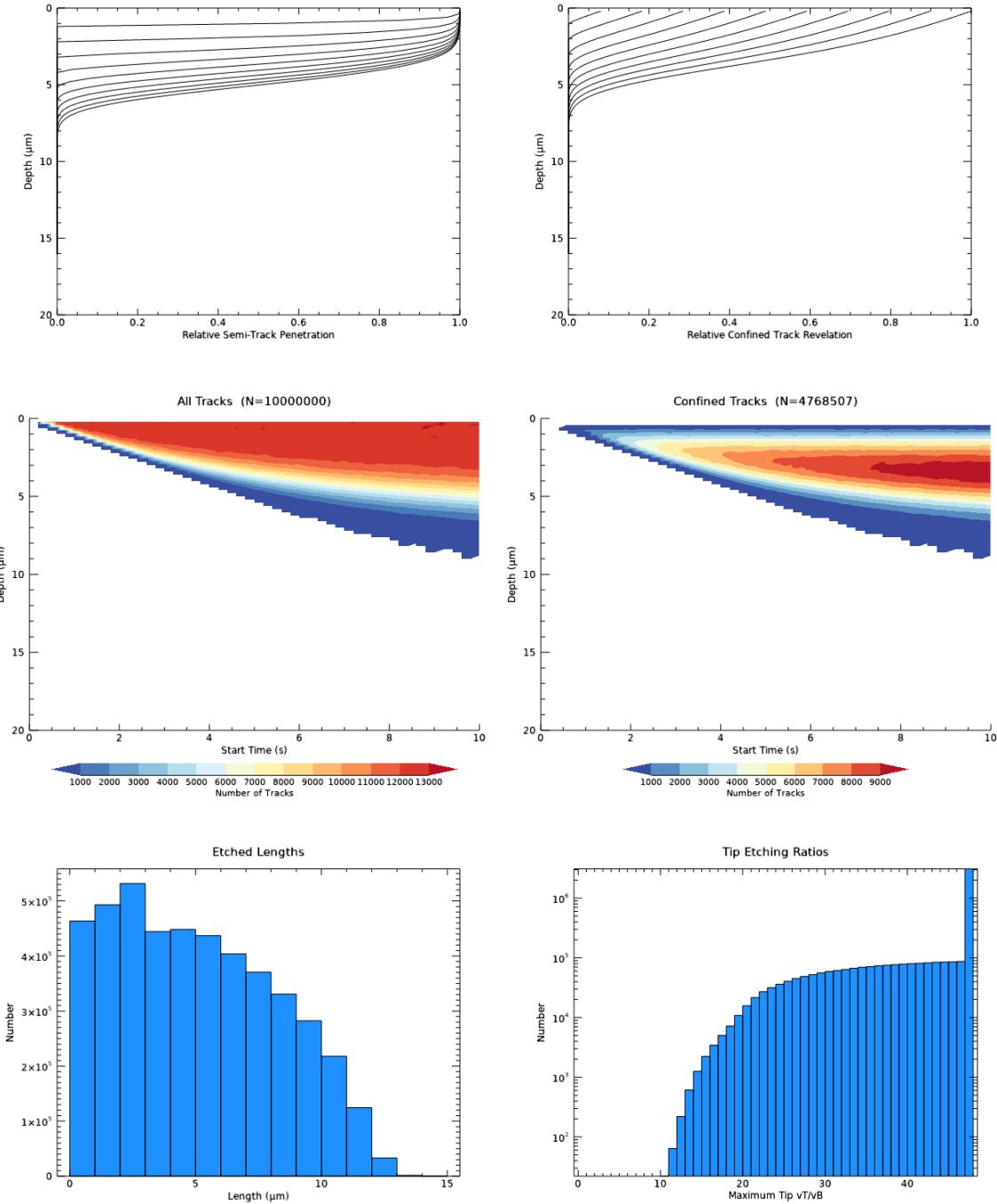


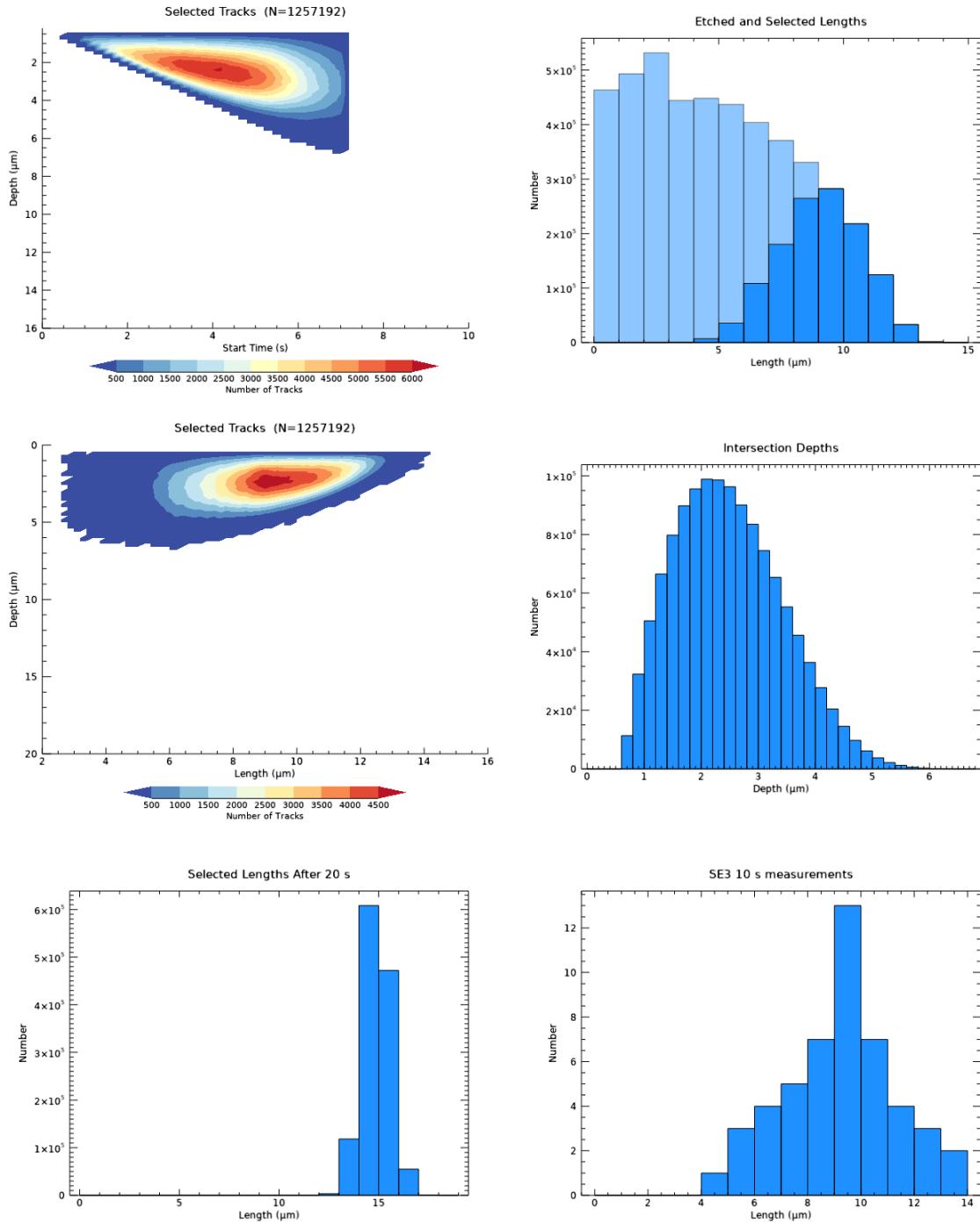
**Figure S-1: Histograms of intersection depths measured in each step-etch and etch-anneal-etch experiment from Tamer and Ketcham (2020). Intersections measured from the final step in the step-etch experiments, and the first step of the etch-anneal-etch experiments (prior to post-etch annealing). Also reported on this figure are the mean depth, mean number of intersections per track, and the spacing of the images captured on the microscope system, from which the measurements were made. Spacings are corrected for the apatite refractive index. More closely spaced images (IA235 and IA270) may have aided in finding more shallow tracks, but also may have biased the measurement procedure against finding deeper ones.**



**Figure S-2: Relationship between etched length after the first etching step, and number of impingements for each data set shown in Fig. S-1. All regressions have a positive slope, indicating that more intersections with etchant pathways is correlated with, and may have helped cause, slightly faster etching. Most of the slopes are low, however, indicating that this was probably at most a minor effect. The one experiment with a strong positive slope was SU-10, which features the slowest overall etching rates.**

## SU-10 model





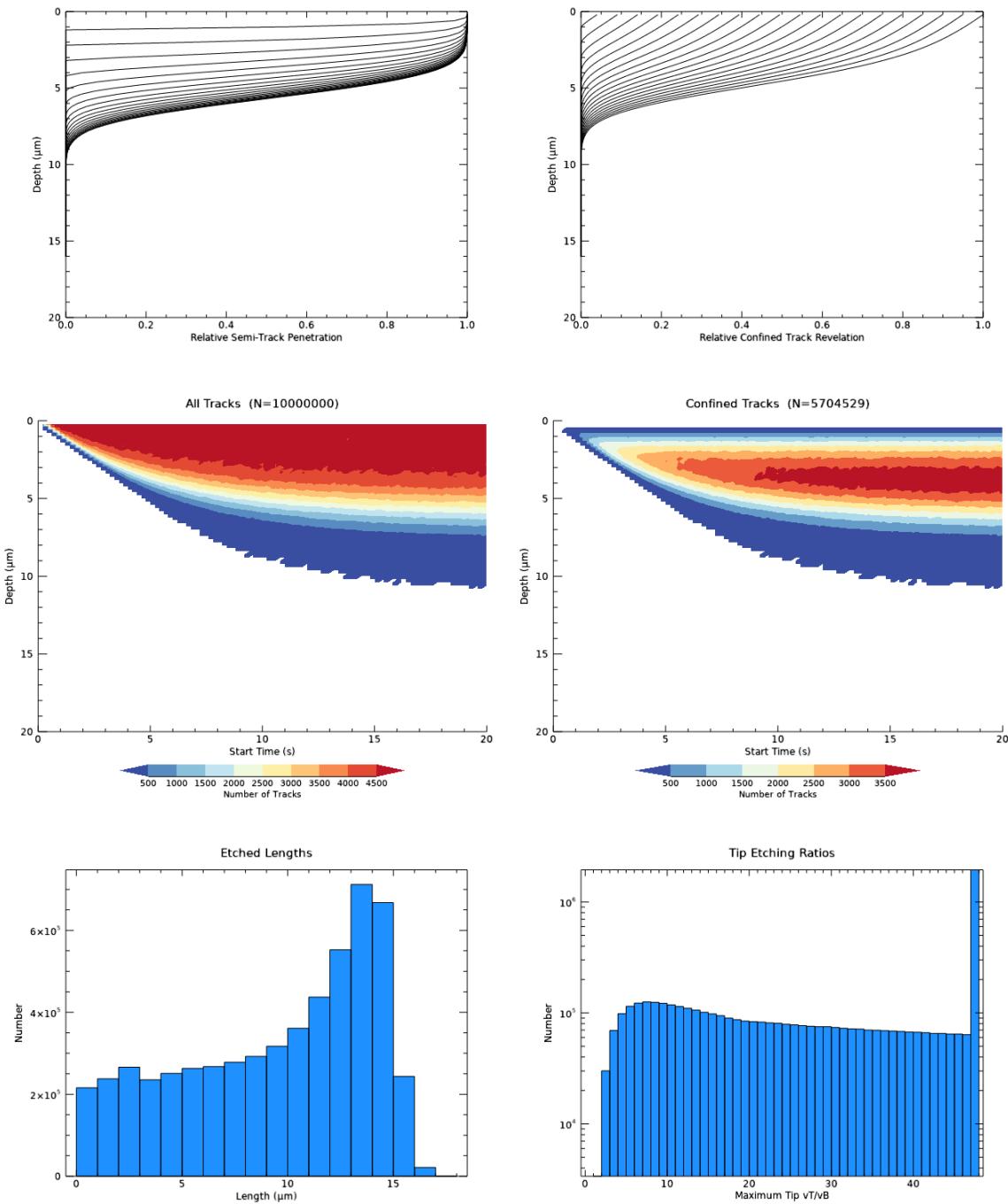
```

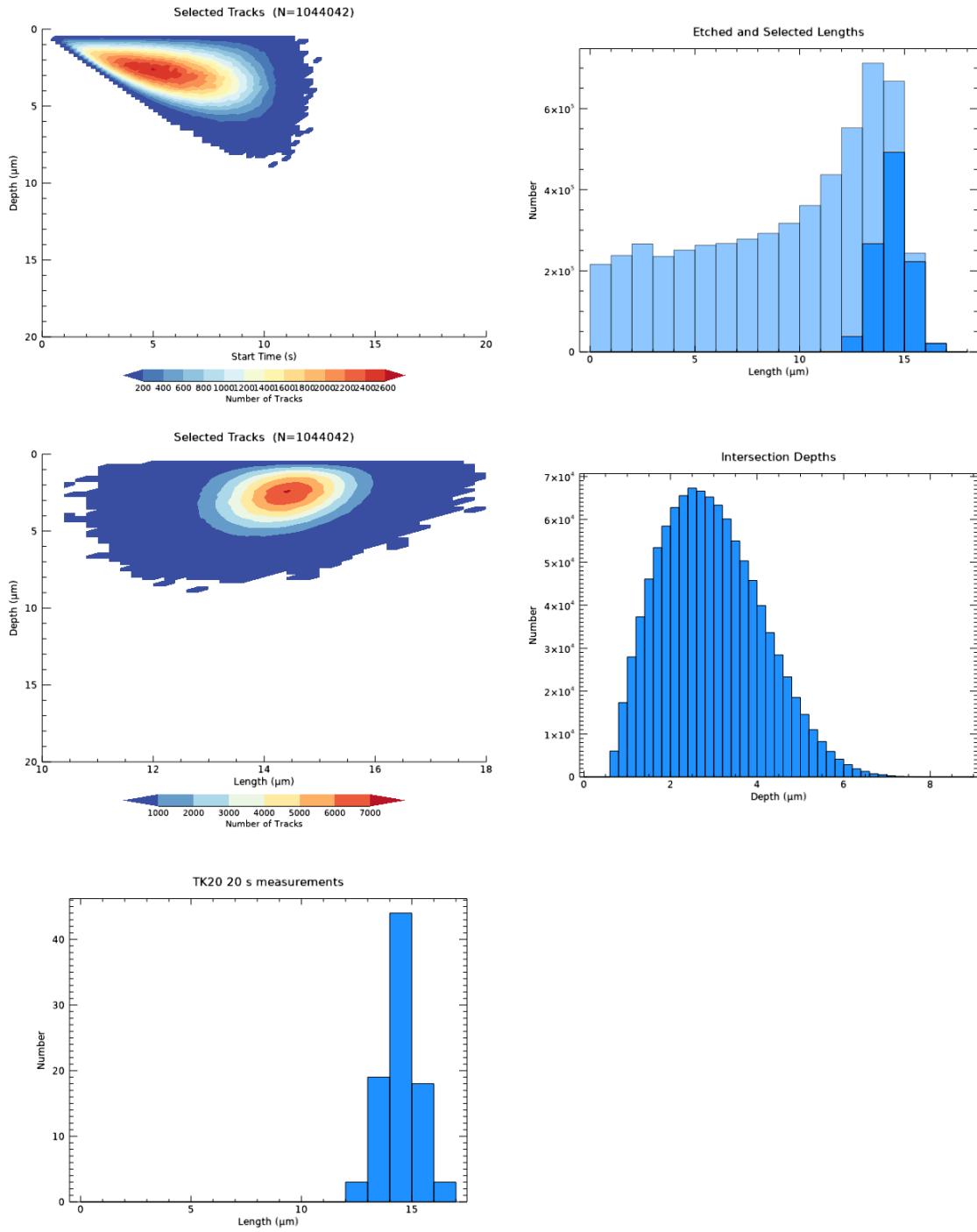
GenerateTrackSet, 0.022, 1.054, 5.48, 5.047, STEPS = [10,15,20,25,30], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000, MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.8, UNDERETCH_BIAS=3., /CF
Etch step      1      9.05054      1.65280      1257192      15.5448      4.40585
2.39043
Etch step      2      13.2873      0.801895     1257192      15.5448      4.40585
2.39043

```

Etch step 2.39043	3	14.8659	0.666287	1257192	15.5448	4.40585
Etch step 2.39043	4	15.4496	0.723828	1257192	15.5448	4.40585
Etch step 2.39043	5	15.7238	0.750228	1257192	15.5448	4.40585

## SU-20 model

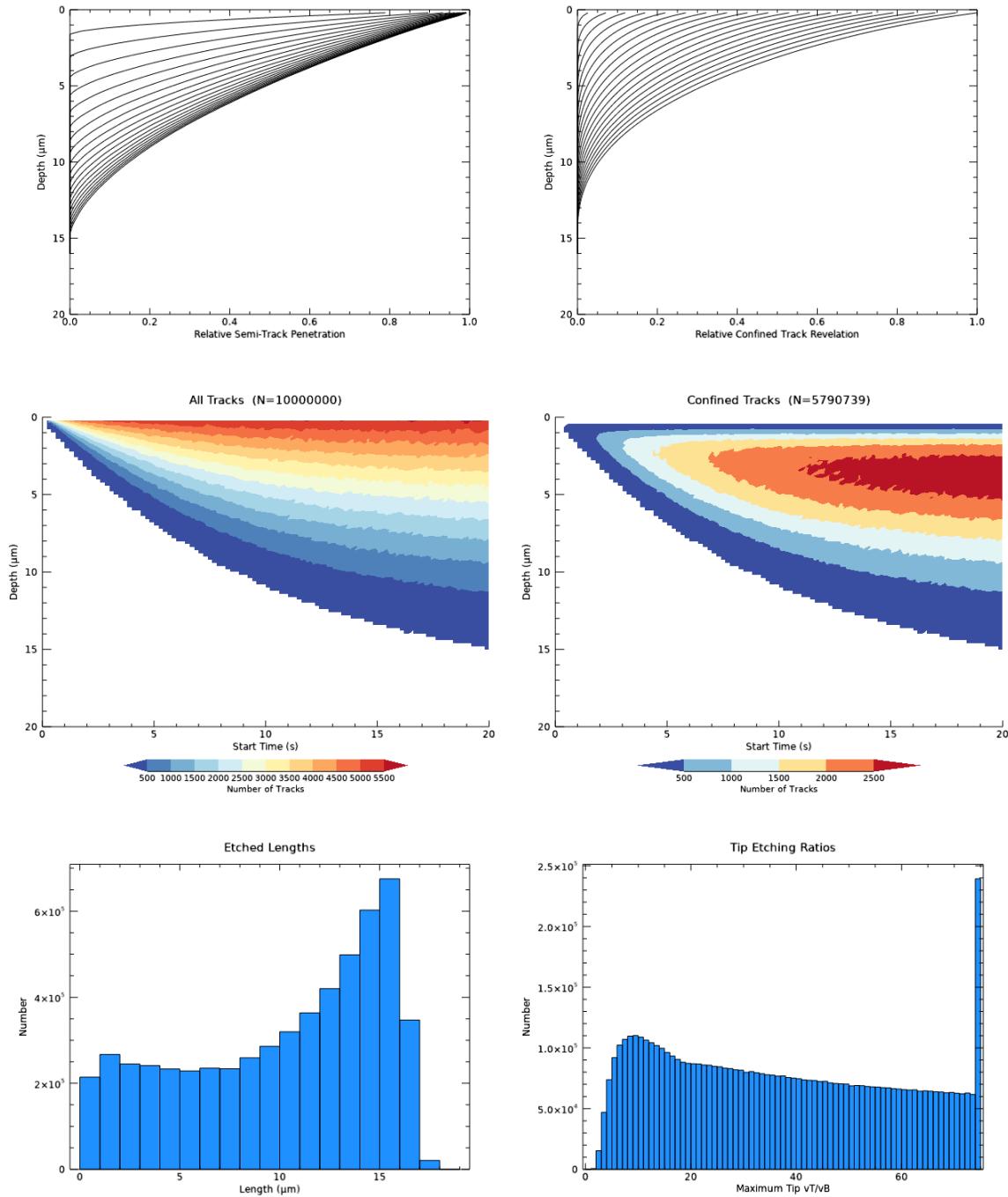


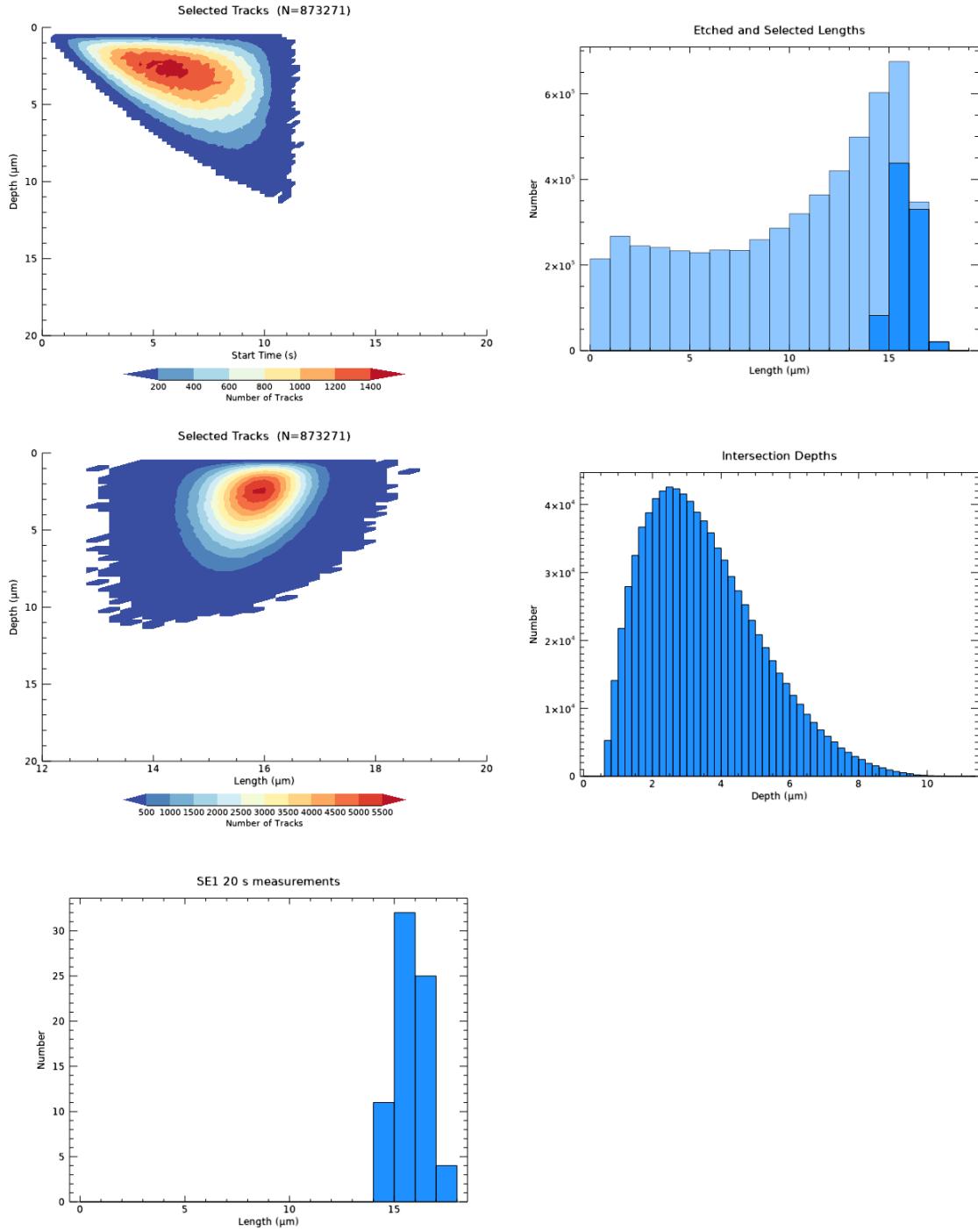


```
GenerateTrackSet, 0.022, 1.054, 5.48, 5.047, STEPS = [20], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000, MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.8, UNDERETCH_BIAS=3., /CF
```

Etch step	1	14.4208	0.789111	1044042	15.4058	6.10189
	2.83534					

## IU-20 model





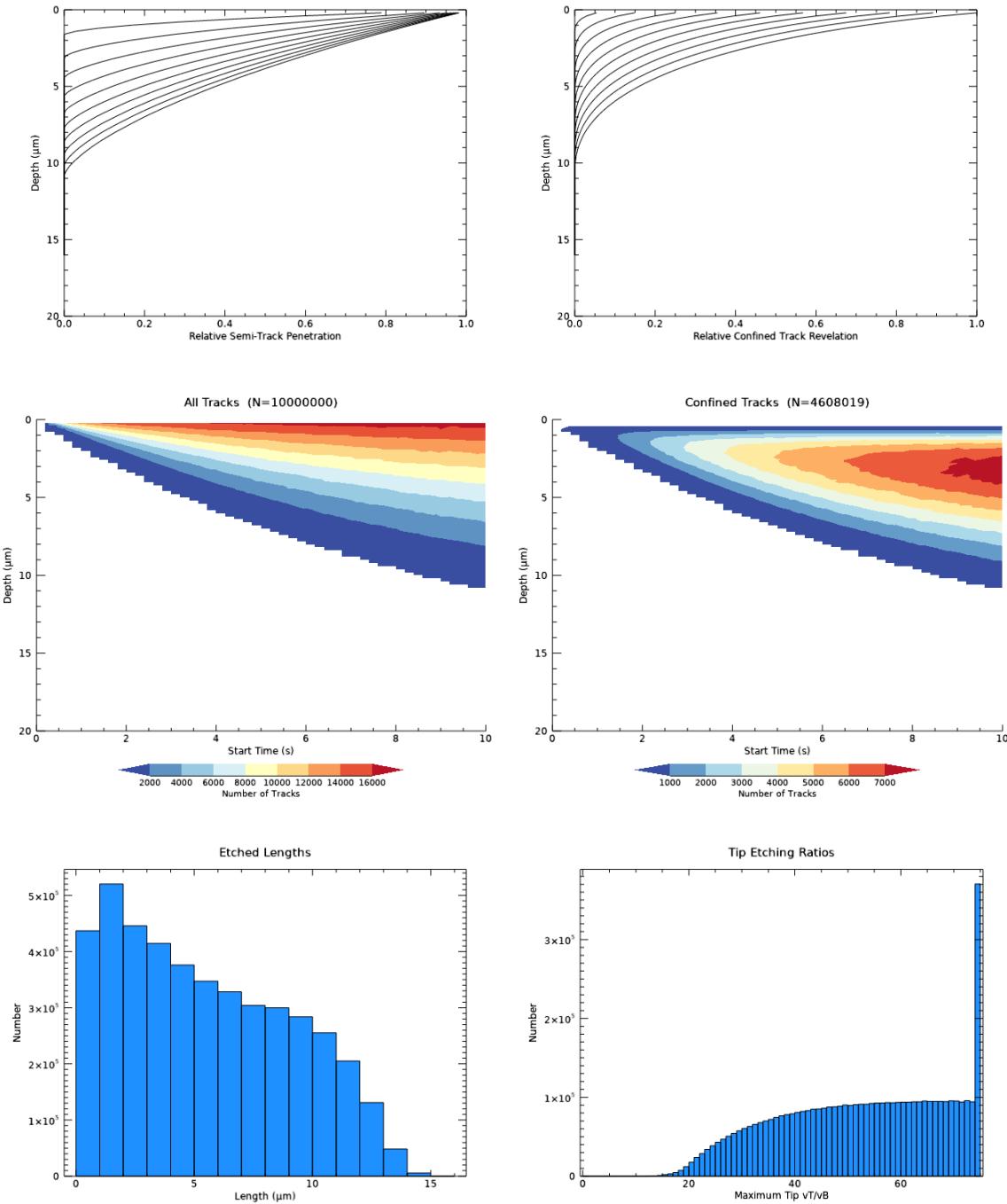
```

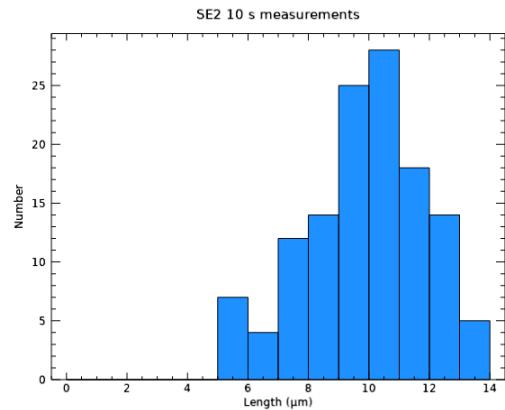
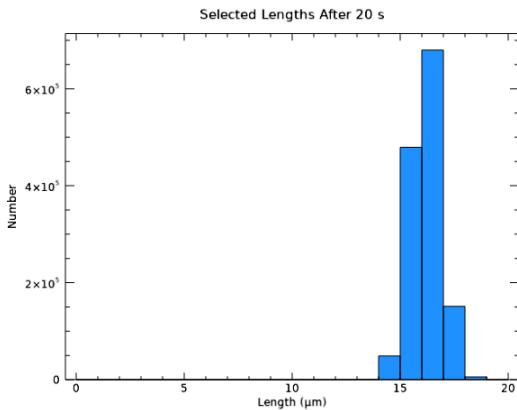
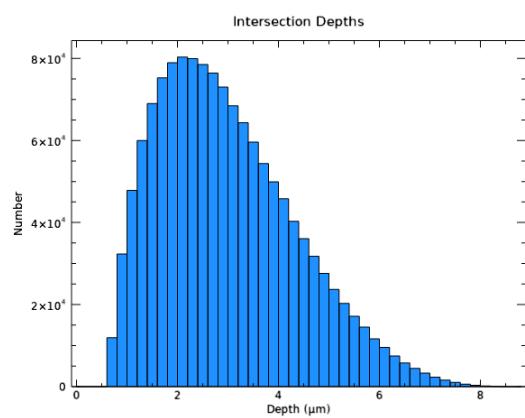
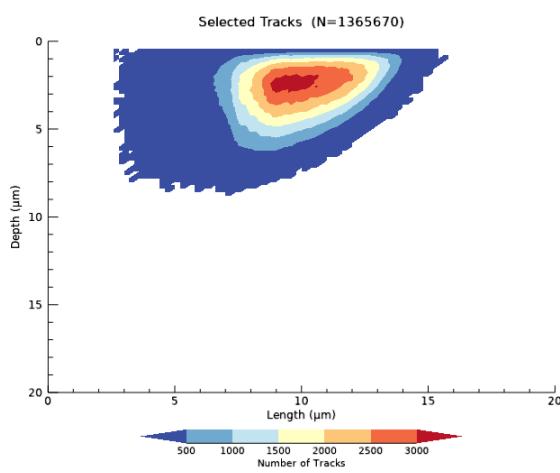
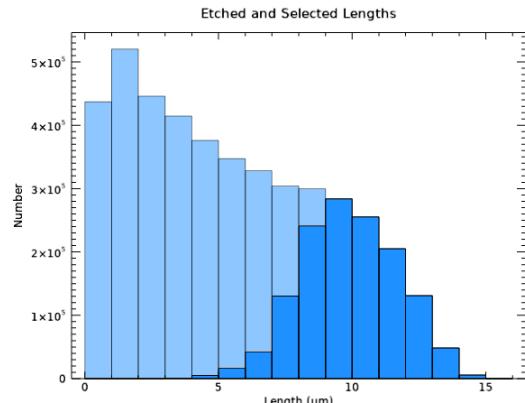
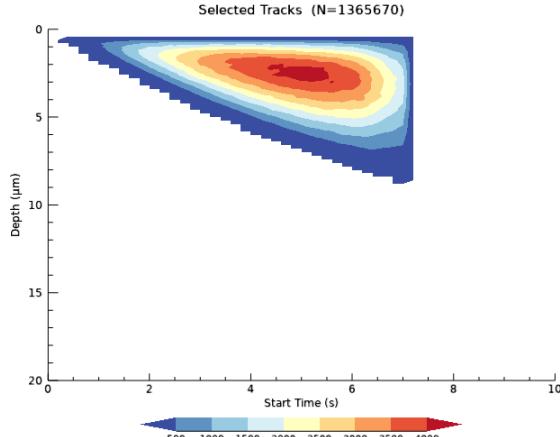
GenerateTrackSet, 0.022, 1.639, 0.74, 8.136, STEPS = [20], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000, MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.5, UNDERETCH_BIAS=3
Etch step      1      15.8290      0.618133      873271      16.9511      6.41710
3.40764
Etch step      2      16.6801      0.489372      873271      16.9511      6.41710
3.40764

```

Etch step	3	17.0241	0.485083	873271	16.9511	6.41710
		3.40764				

## IU-10 model



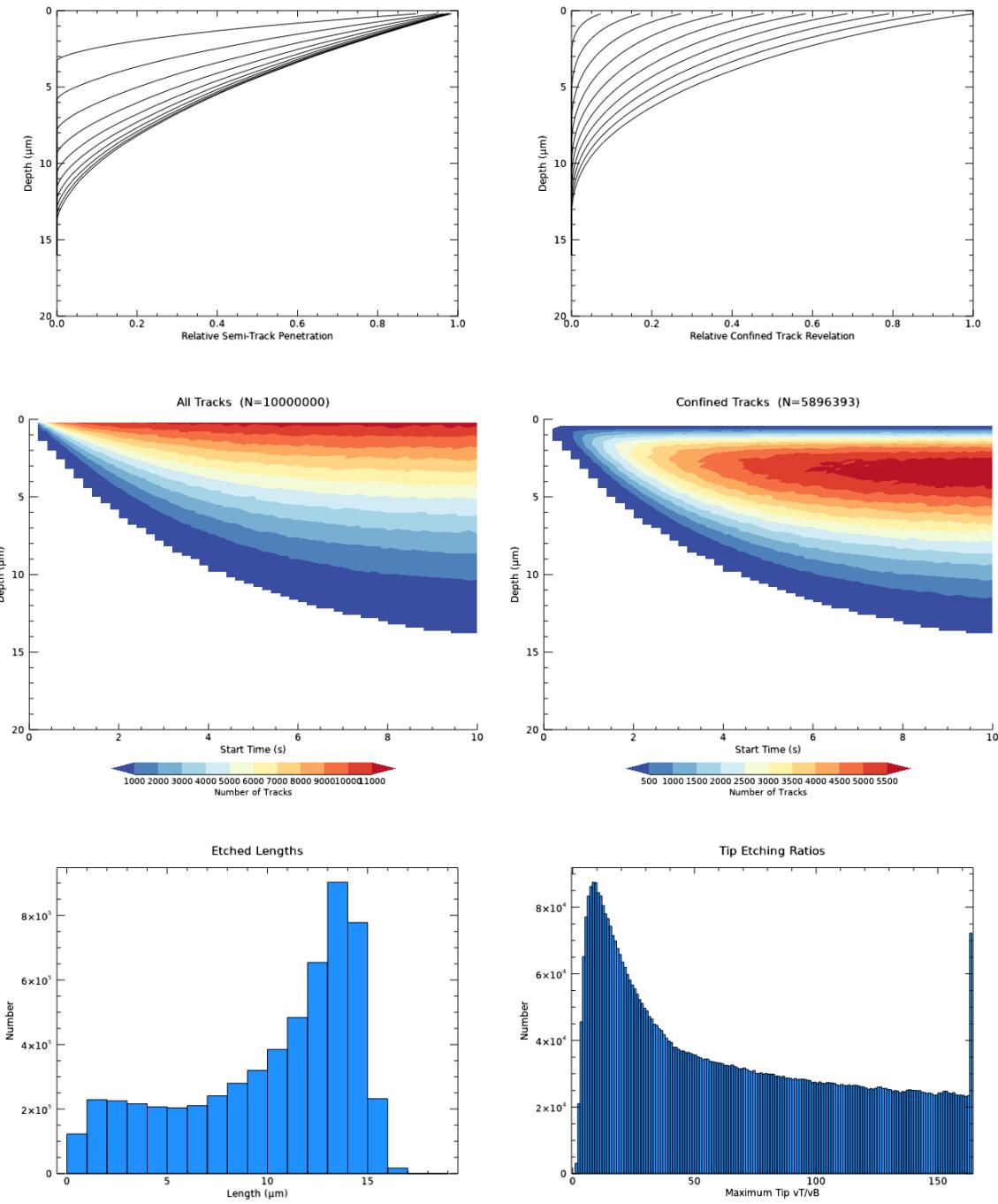


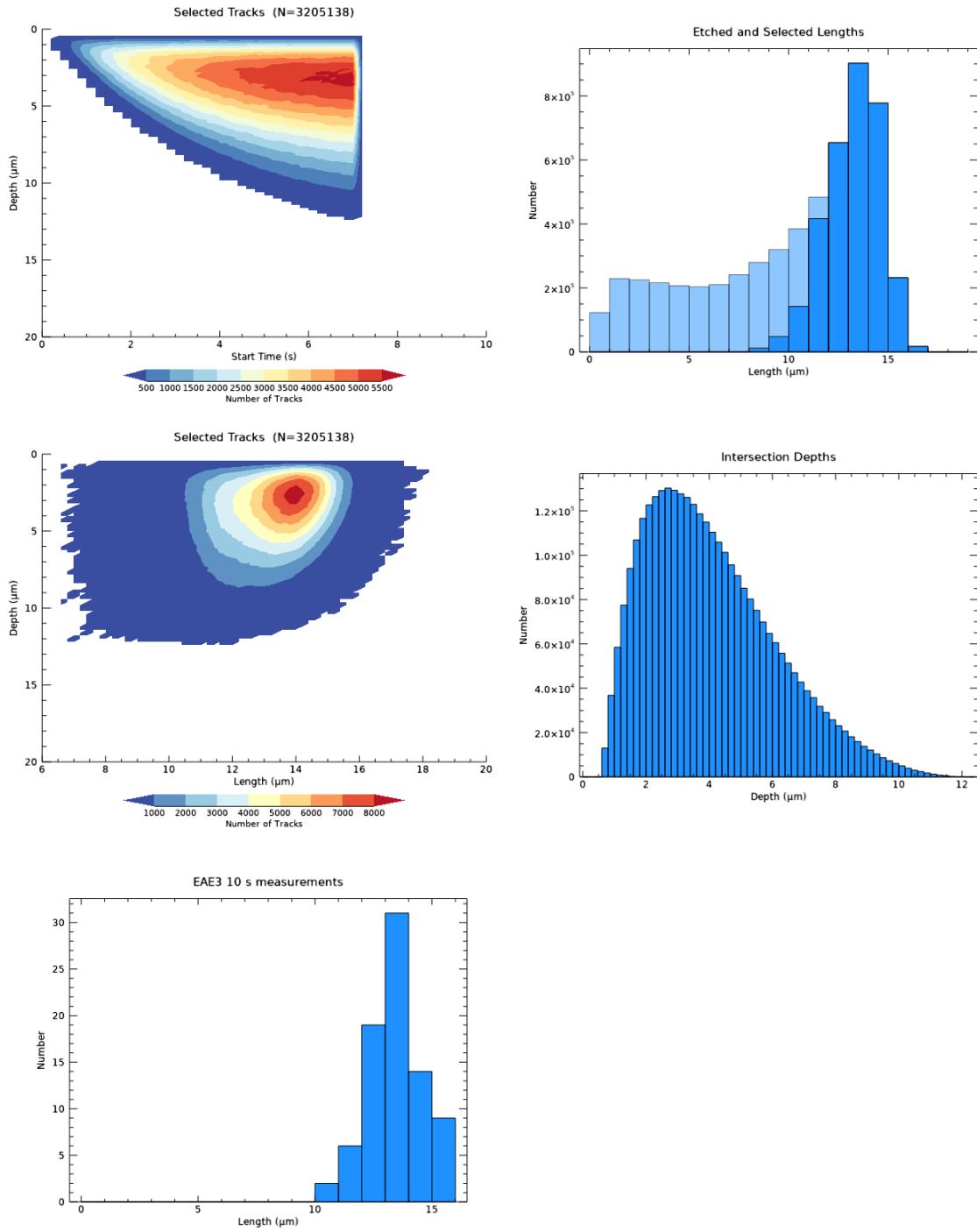
**GenerateTrackSet**, **0.022**, **1.639**, **0.74**, **8.136**, STEPS = [**10,20,25,30**], DEPTH\_INC=**0.2**, TIME\_INC=**0.2**, EX\_TIP=**2.**, NUM\_TRACKS=**10000000**, MAX\_DIP=**25.**, MAX\_TIP\_VTVB=**12.**, SD\_LEN=**0.8**, UNDERETCH\_BIAS=**3.**

Etch step	1	9.90717	1.79459	1365670	16.9808	4.83815
2.87876						
Etch step	2	16.1950	0.670720	1365670	16.9808	4.83815
	2.87876					

Etch step	3	16.8354	0.725324	1365670	16.9808	4.83815
2.87876						
Etch step	4	17.1230	0.753539	1365670	16.9808	4.83815
2.87876						

## IA235-10 model

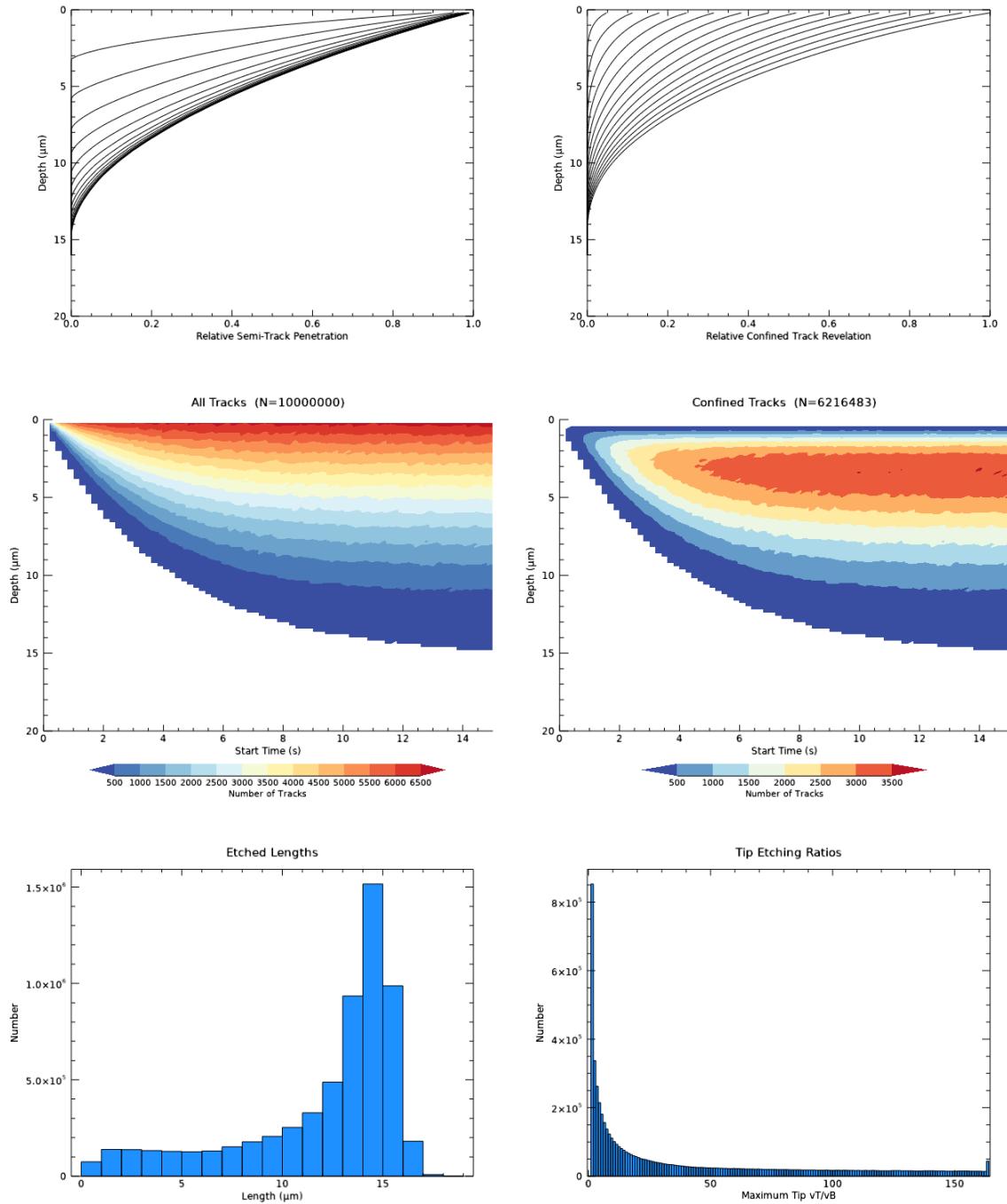


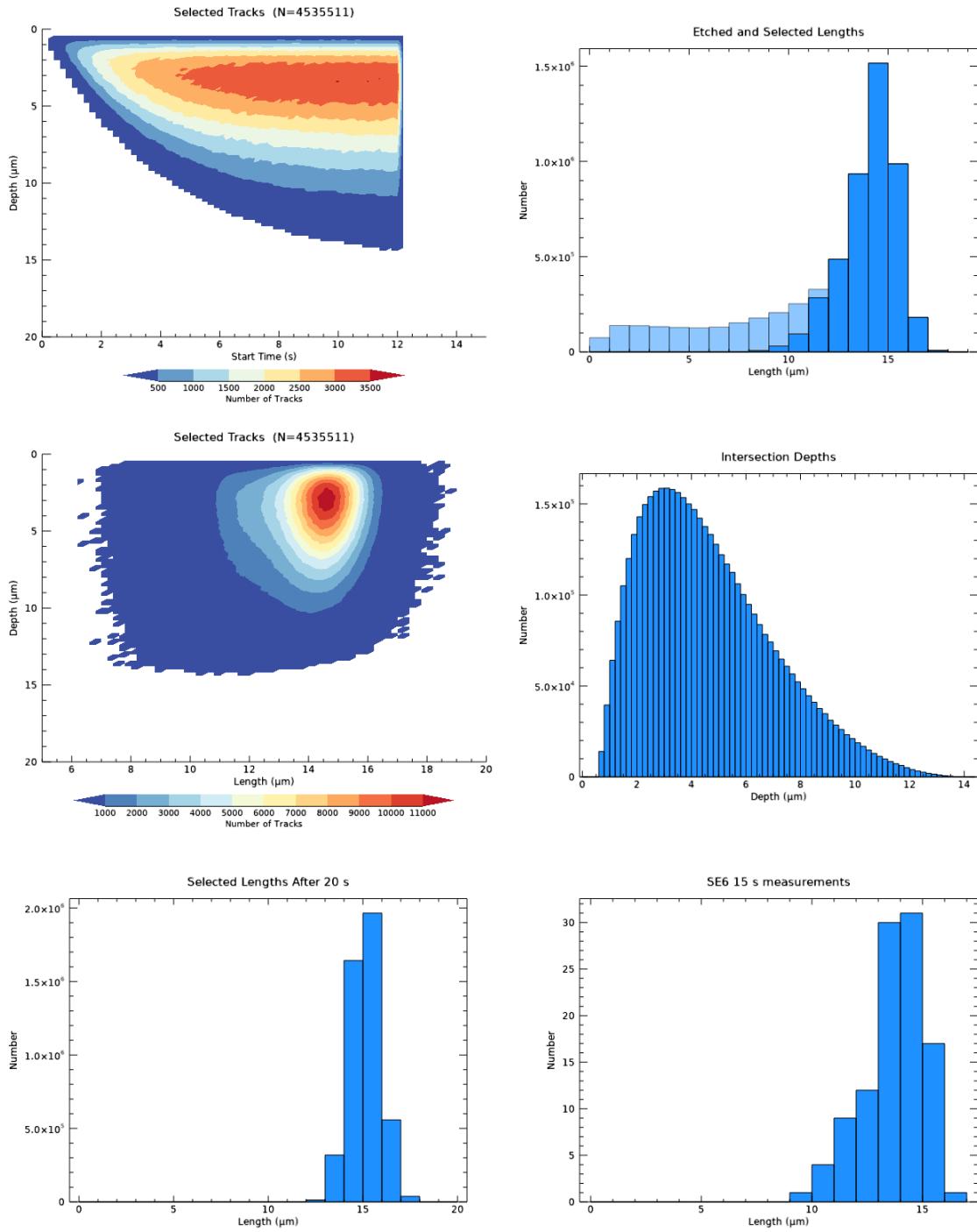


```
GenerateTrackSet, 0.022, 3.592, 0.26, 7.418, STEPS = [10], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000, MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.8, UNDERETCH_BIAS=3.
```

Etch step	1	13.2255	1.37634	3205138	15.0789	4.82783
				3.97398		

## IA235-15 model



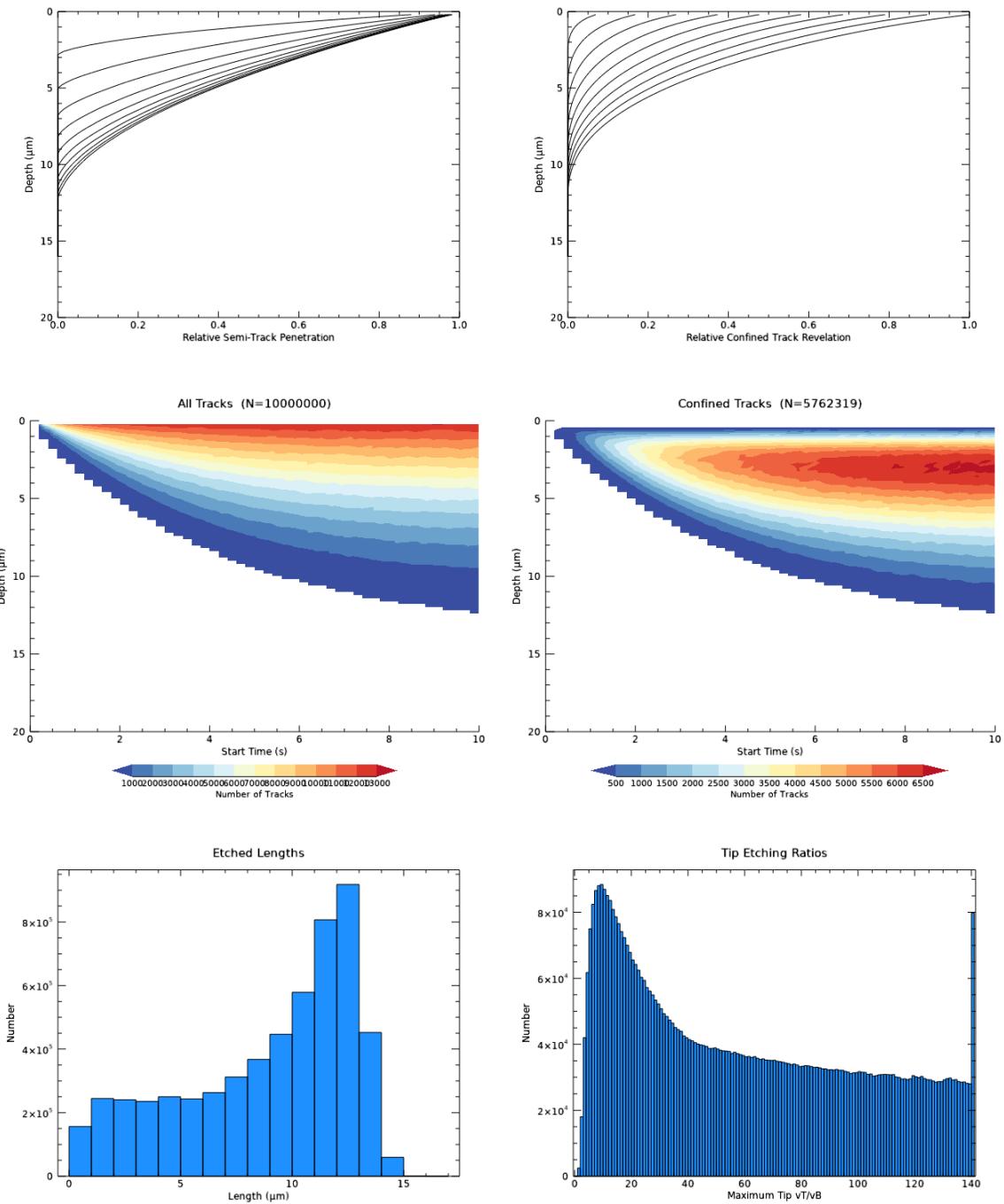


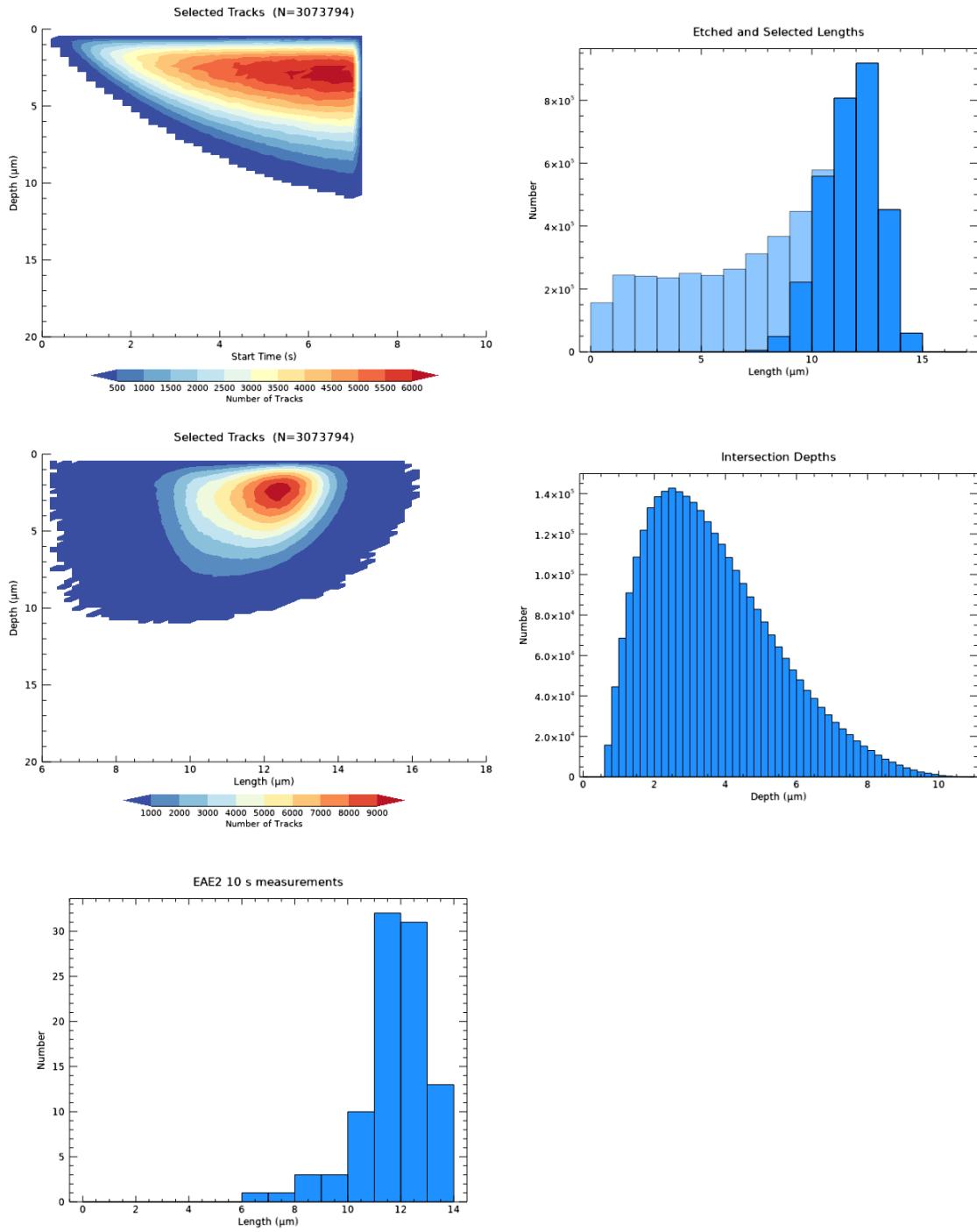
```
GenerateTrackSet, 0.022, 3.592, 0.26, 7.418, STEPS = [15,20,25,30], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000, MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.8, UNDERETCH_BIAS=3.
```

Etch step	1	14.0627	1.37989	4535511	15.0806	7.66058
						4.52818

Etch step	2	15.1282	0.778208	4535511	15.0806	7.66058
4.52818						
Etch step	3	15.3774	0.784190	4535511	15.0806	7.66058
4.52818						
Etch step	4	15.5980	0.784217	4535511	15.0806	7.66058
4.52818						

## IA270-10 model

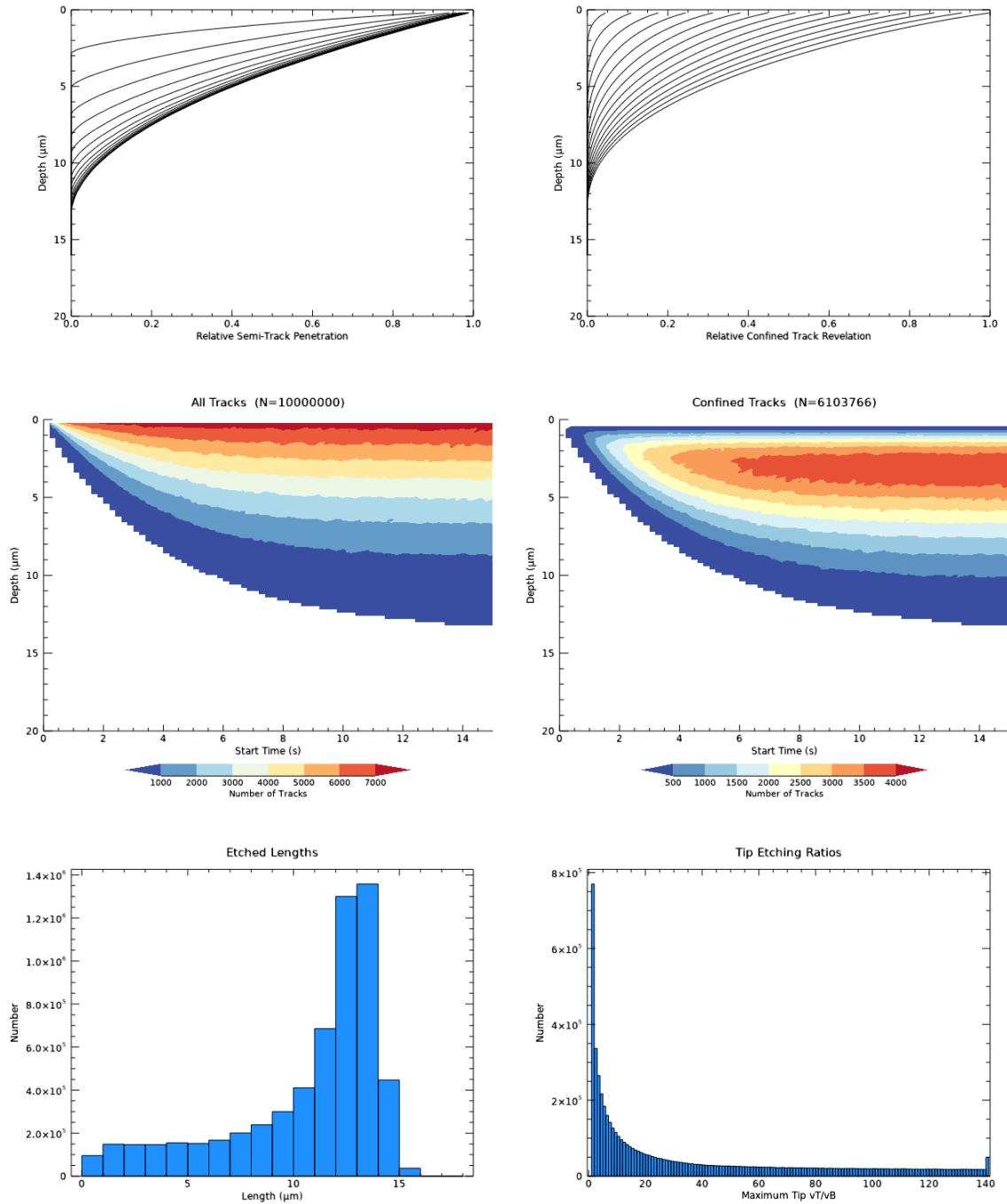


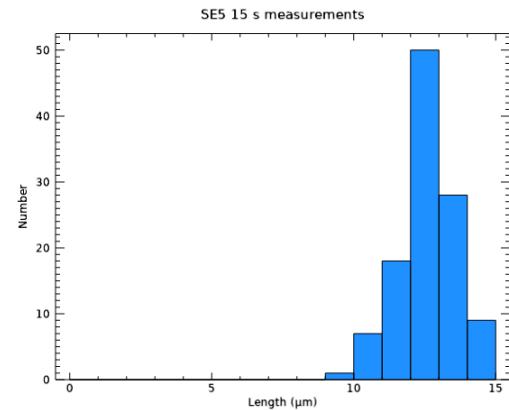
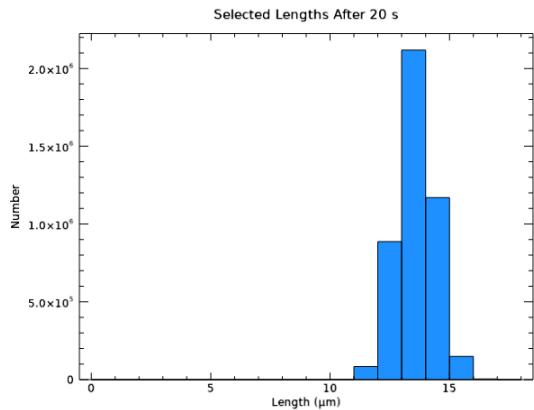
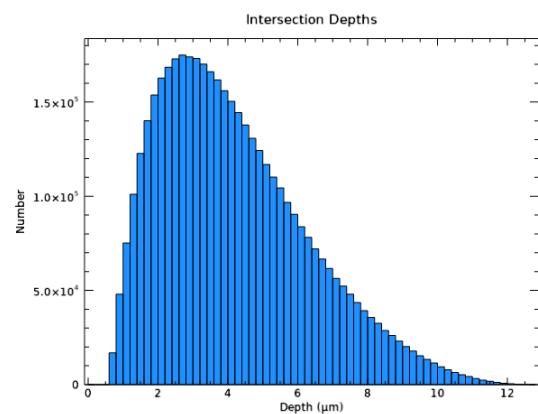
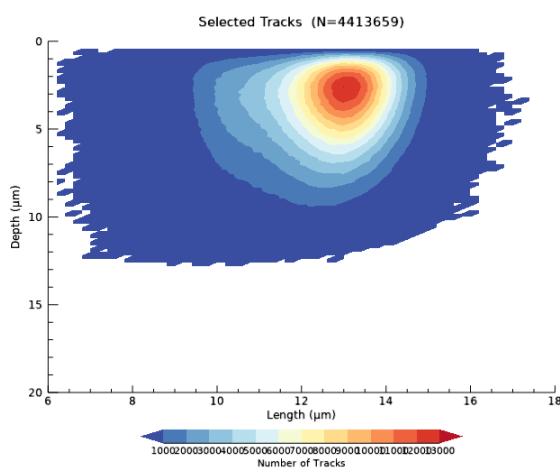
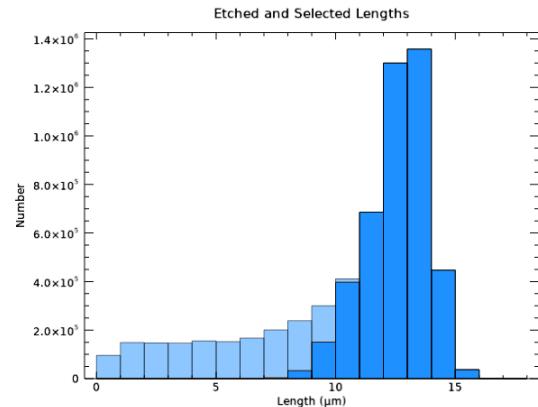
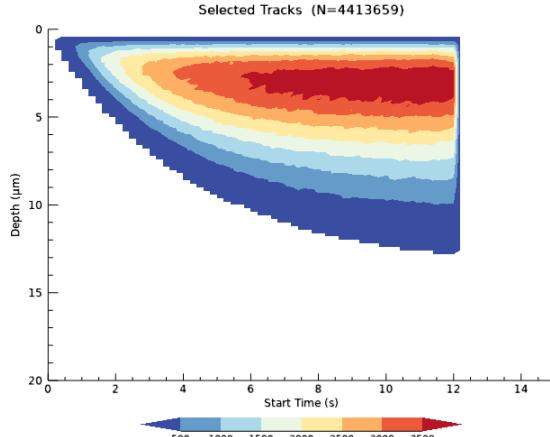


```
GenerateTrackSet, 0.022, 3.083, 0.26, 6.659, STEPS = [10], DEPTH_INC=0.2,
TIME_INC=0.2, EX_TIP=2., NUM_TRACKS=10000000,MAX_DIP=25., MAX_TIP_VTVB=12.,
SD_LEN=0.8, UNDERETCH_BIAS=3.
```

Etch step	1	11.7698	1.24949	3073794	13.5570	4.85649
	3.56681					

## IA270-15 model



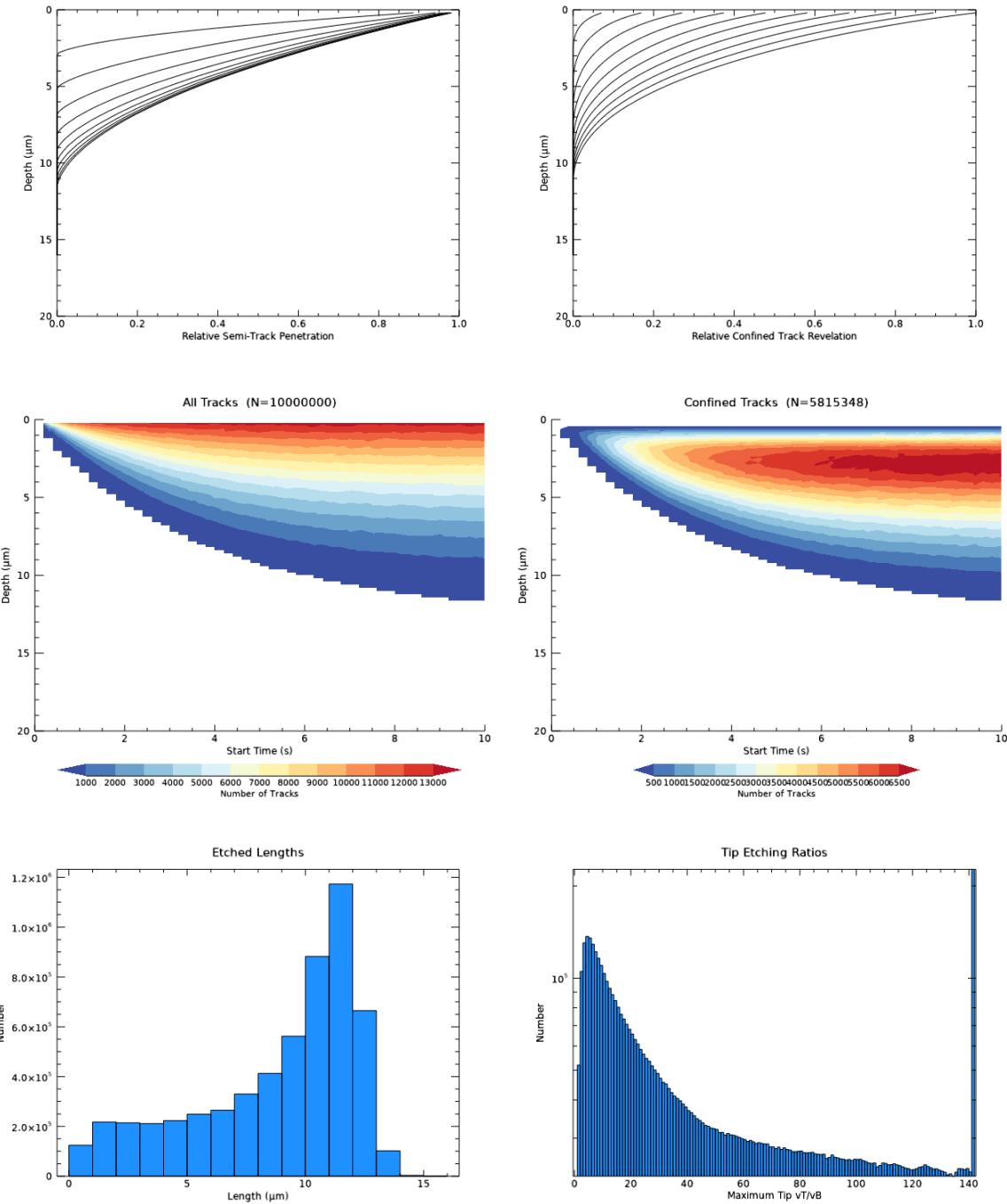


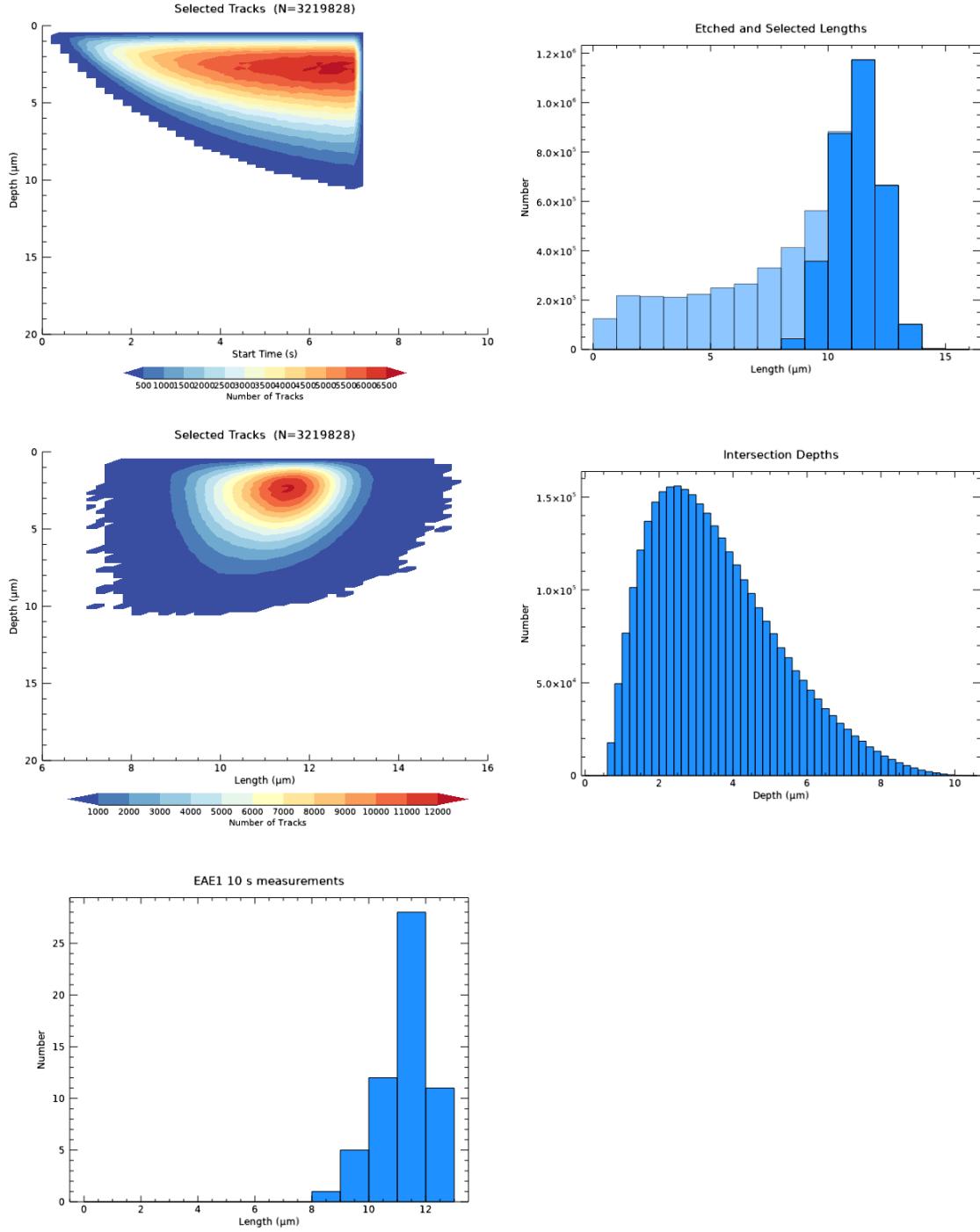
**GenerateTrackSet**, **0.022**, **3.083**, **0.26**, **6.659**, STEPS = [**15,20,25,30**], DEPTH\_INC=**0.2**, TIME\_INC=**0.2**, EX\_TIP=**2.**, NUM\_TRACKS=**10000000**, MAX\_DIP=**25.**, MAX\_TIP\_VTVB=**12.**, SD\_LEN=**0.8**, UNDERETCH\_BIAS=**3.**

Etch step 4.09157	1	12.5617	1.29227	4413659	13.5603	7.71907
Etch step 4.09157	2	13.5957	0.772601	4413659	13.5603	7.71907

Etch step	3	13.8464	0.780455	4413659	13.5603	7.71907
4.09157						
Etch step	4	14.0661	0.780500	4413659	13.5603	7.71907
4.09157						

## IA280-10 model

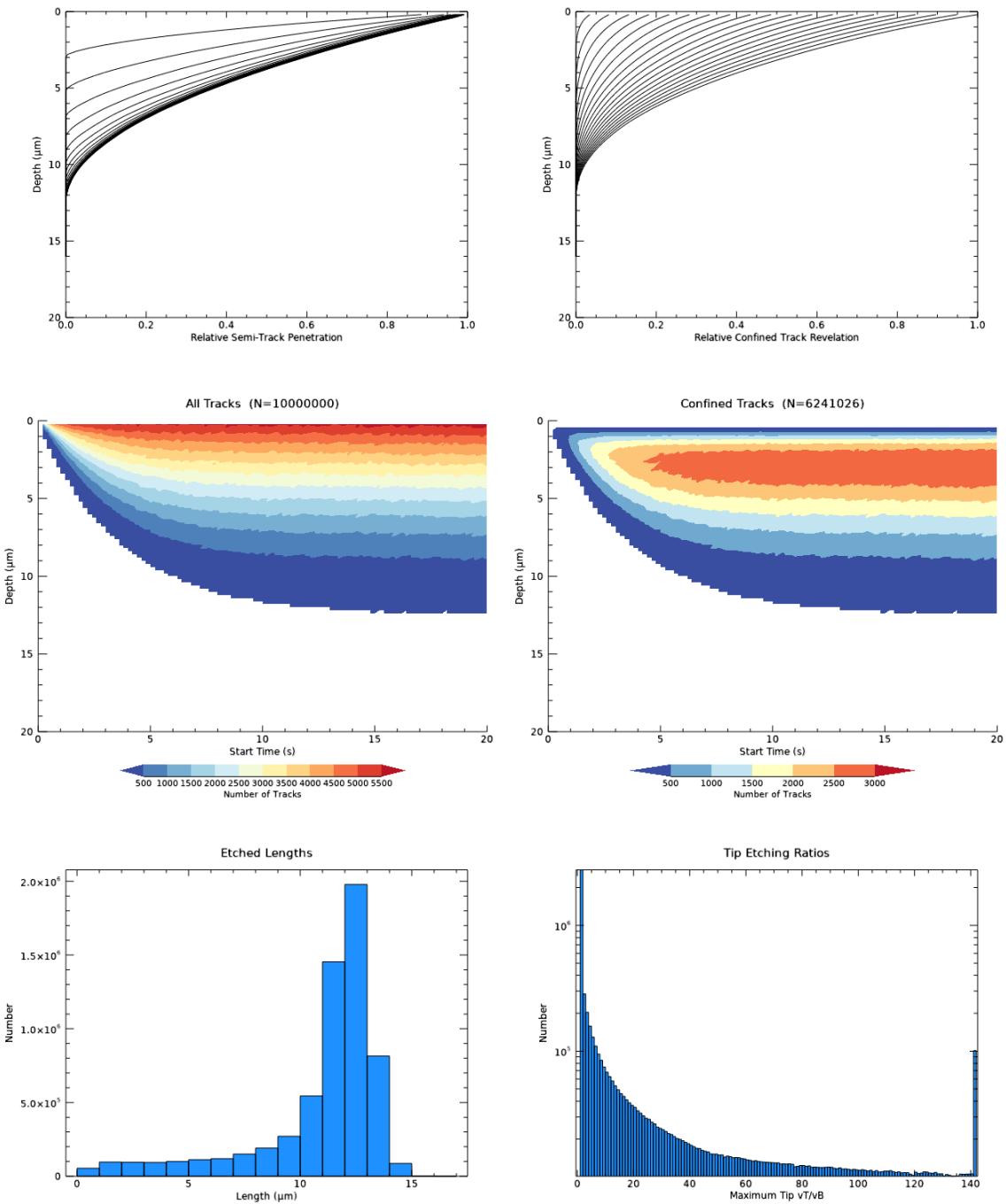


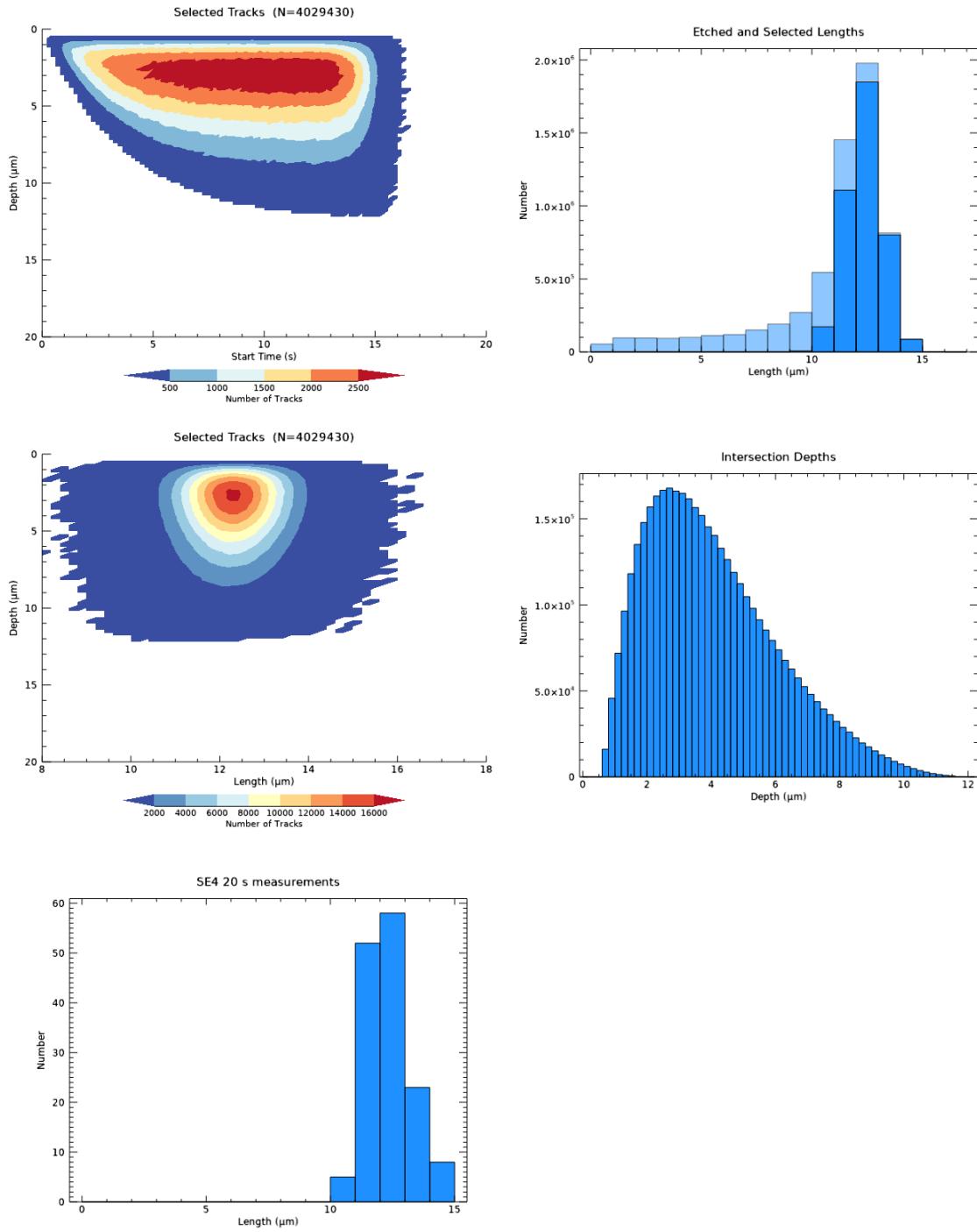


**GenerateTrackSet, 0.022, 3.109, 0.78, 5.810, STEPS=[10], DEPTH\_INC=0.2, TIME\_INC=0.2, EX\_TIP=2., NUM\_TRACKS=10000000, MAX\_DIP=25., MAX\_TIP\_VTVB=12., SD\_LEN=0.8, UNDERETCH\_BIAS=3.**

Parameter	Value
Etch step	1
	11.2377
	1.01552
	3219828
	12.3797
	4.79518
	3.44276

## IA280-20 model





**GenerateTrackSet**, **0.022**, **3.109**, **0.78**, **5.810**, STEPS = [**20,25,30**], DEPTH\_INC=**0.2**, TIME\_INC=**0.2**, EX\_TIP=**2.**, NUM\_TRACKS=**10000000**, MAX\_DIP=**25.**, MAX\_TIP\_VTVB=**12.**, SD\_LEN=**0.8**, UNDERETCH\_BIAS=**3**.

Etch step 3.94890	1	12.3775	0.808697	4029430	12.3519	8.82009
Etch step 3.94890	2	12.6498	0.795843	4029430	12.3519	8.82009

Etch step	3	12.8698	0.795844	4029430	12.3519	8.82009
		3.94890				